AMENDMENTS TO THE CLAIMS:

1. (Currently Amended) A measuring system of a gas-stream environment, said measuring system of the gas stream environment comprising:

a ~~stage, said~~ stage ~~locating~~ located on a transport apparatus and a wafer ~~placing~~ placed on said stage;

a ~~datum platen, said~~ datum platen ~~locating~~ located on said transport apparatus and on a side of said stage ~~to place~~ for placement of a datum slice, wherein said datum slice is a measuring reference point;

a ~~lens, said~~ lens ~~locating~~ located above said ~~stage~~ stage that is used in measurement of ~~to measure the~~ a thickness of said wafer and said datum slice;

a ~~gas supplier, said~~ gas supplier ~~supplying a gas~~ used to supply a gas;

a ~~first gas nozzle, said~~ first gas nozzle ~~locating~~ located on a side of said datum platen;

a ~~second gas nozzle, said~~ second gas nozzle ~~locating~~ located on a side of said stage;

a ~~first tube, said~~ first tube ~~connecting~~ connected with said first gas nozzle and said gas supplier;

a ~~second tube, said~~ second tube ~~connecting~~ connected with said second gas nozzle and with said gas suppler, wherein said gas supplier ~~supplied~~ supplies said gas ~~passing~~ that passes through said first tube and said second tube, and ~~exhausted~~ exhausts from said first gas nozzle and said second gas nozzle to form a gas stream;

a ~~transport slot, said~~ transport slot ~~collecting~~ which collects said gas in said gas stream, and ~~using a~~ which uses a channel to exhaust said gas stream; and

a gas-extracting apparatus, said gas-extracting apparatus ~~connecting~~ being connected with said transport slot by using a third tube.

2. (Currently Amended) The measuring system of the gas stream environment according to claim 1, further comprising a first flow rate regulating valve ~~fixing~~ fixed on said first gas nozzle.

3. (Currently Amended) The measuring system of the gas stream environment according to claim 1, further comprising a second flow rate regulating valve ~~fixing~~ fixed on said second gas nozzle.

4. (Currently Amended) The measuring system of the gas stream environment according to claim 2, wherein said gas-extracting apparatus comprises a gas-extracting motor.

5. (Currently Amended) The measuring system of the gas stream environment according to claim 1, wherein said gas-extracting apparatus comprises a ~~venture~~ Venturi structure.

6. (Currently Amended) The measuring system of the gas stream environment according to claim 1, wherein said gas is an inert gas.

7. (Currently Amended) The measuring system of the gas stream environment according to claim 1, wherein said gas is nitrogen.

8. (Canceled)

9. (Currently Amended) A measuring system of a gas-stream environment, said measuring system of the gas stream environment comprising:

a ~~stage, said~~ stage ~~locating~~ located on a transport apparatus and a wafer ~~placing~~ placed on said stage;

a ~~datum platen, said~~ datum platen ~~locating~~ located on said transport apparatus and on a side of said stage ~~to place~~ for placement of a datum slice, wherein said datum slice is a measuring reference point;

a ~~lens, said~~ lens ~~locating~~ located above said stage that is used ~~to measure the~~ in a measurement of a thickness of said wafer and said datum slice;

a ~~gas supplier, said~~ gas supplier ~~supplying a gas~~ used to supply a gas;

a ~~first gas nozzle, said~~ first gas nozzle ~~locating~~ located on a side of said datum platen;

a ~~second gas nozzle, said~~ second gas nozzle ~~locating~~ located on a side of said stage;

a ~~first tube, said~~ first tube ~~connecting~~ connected with said first gas nozzle and with said gas supplier;

a ~~second tube, said~~ second tube ~~connecting~~ connected with said second gas nozzle and with said gas suppler, wherein said gas supplier ~~supplied~~ supplies said gas ~~passing~~ that passes through said first tube and said second tube, and ~~exhausted~~ exhausts from said first gas nozzle and said second gas nozzle to form a gas stream;

a ~~transport slot, said~~ transport slot ~~extracting~~ which extracts said gas; and

a gas-extracting apparatus, said gas-extracting apparatus ~~connecting~~ being connected with said transport slot by using a third tube.

10. (Currently Amended) The measuring system of the gas stream environment according to claim 9, wherein said first tube comprises a first flow rate regulating valve.

11. (Currently Amended) The measuring system of the gas stream environment according to claim 9, wherein said second tube comprises a second flow rate regulating valve.

12. (Currently Amended) The measuring system of the gas stream environment according to claim 9, wherein said gas-extracting apparatus comprises a gas-extracting motor.

13. (Currently Amended) The measuring system of the gas stream environment according to claim 9, wherein said gas-extracting apparatus comprises a ~~venture~~ Venturi structure.

14. (Currently Amended) The measuring system of the gas stream environment according to claim 9, wherein said gas is an inert gas.

15. (Currently Amended) The measuring system of the gas stream environment according to claim 9, wherein said gas is a nitrogen.

16. (Canceled)

17. (Currently Amended) A measuring system of a gas-stream environment, said measuring system comprising:

a ~~stage, said~~ stage ~~locating~~ located on a transport apparatus and a wafer ~~placing~~ placed on said stage;

a ~~datum platen, said~~ datum platen ~~locating~~ located on said transport apparatus and on a side of said stage ~~to place~~ for placement of a datum slice;

a ~~lens, said~~ lens ~~locating~~ located above said stage that is used in a measurement of ~~to measure the~~ a thickness of said wafer and said datum slice;

a ~~gas supplier, said~~ gas supplier ~~supplying a gas~~ used to supply a gas;

a ~~first gas nozzle, said~~ first gas nozzle ~~locating~~ located on a side of said datum platen and on said transport apparatus to exhaust said gas;

a ~~second gas nozzle, said~~ second gas nozzle ~~locating~~ located on a side of said stage and on said transport apparatus to exhaust said gas in said gas stream;

a ~~first tube, said~~ first tube having a first flow rate regulating valve, and ~~connecting~~ connected with said first gas nozzle and with said gas supplier;

a ~~second tube, said~~ second tube having a second flow rate regulating valve and ~~connecting~~ connected with said second gas nozzle and with said gas suppler;

a ~~transport slot, said~~ transport slot ~~is~~ comprising an opening to exhaust said gas; and

a gas-extracting apparatus, said gas-extracting apparatus ~~connecting~~ being connected with said transport slot by using a third tube and producing an attraction to remove said gas.

18. (Currently Amended) The measuring system of the gas stream environment according to claim 17, wherein said gas-extracting apparatus comprises a ~~venture~~ Venturi structure.

19. (Currently Amended) The measuring system of the gas stream environment according to claim 17, wherein said gas in an inert.

20. (Currently Amended) The measuring system of the gas stream environment ~~measuring system~~ accordingly to claim 17, wherein said gas is nitrogen.

21. (Currently Amended) The measuring system of the gas stream environment according to claim 1, wherein said first gas nozzle used to exhaust a gas in a gas stream.

22. (Currently Amended) The measuring system of the gas stream environment according to claim 1, wherein said transport slot is used to collect said gas in said gas stream.

23. (Currently Amended) The measuring system of the gas stream environment according to claim 1, wherein said transport slot is used ~~to be~~ as a channel to exhaust said gas in said gas stream.

24. (Currently Amended) The measuring system of the gas stream environment according to claim 1, ~~wherein said lens to measure said thickness of said wafer comprises~~ further comprising:

means for placing said wafer on said stage;

wherein said stage is moved to a place under said lens using said transport apparatus ~~by using a robot~~; and

~~moving said stage to the place under said lens by using said transport device~~;

means for irradiating ~~a light from said lens to~~ a surface of said wafer and the ~~data~~ datum slice,

wherein ~~said~~ data returned from said irradiation is ~~returned from said light and showed~~ shown on a monitor; and

wherein ~~analyzing~~ said data is analyzed to obtain said thickness of said wafer.

25. (Currently Amended) The measuring system of the gas stream environment according to claim 9, ~~wherein said lens to measure said thickness of said wafer comprises~~ further comprising:

means for placing said wafer on said stage ~~by using a robot~~;

wherein said stage is moved to a place under said lens ~~moving said stage to the place under said lens by~~ using said transport ~~device~~ apparatus; and

means for irradiating ~~a light from said lens to~~ a surface of said wafer and the ~~data~~ datum slice,

wherein ~~said~~ data returned from said irradiation is ~~returned from said light and showed~~ shown on a monitor; and

wherein ~~analyzing~~ said data is analyzed to obtain said thickness of said wafer.

26. (Currently Amended) The measuring system of the gas stream environment according to claim 17, ~~wherein said lens to measure said thickness of said wafer comprises~~ further comprising:

means for placing said wafer on said stage ~~by using a robot~~;

~~moving said stage to the~~ ~~place under said lens by using said transport device~~;

wherein said stage is moved to a place under said lens using said transport apparatus; and

means for irradiating ~~a light from said lens to~~ a surface of said wafer and the ~~data~~ datum slice,

wherein ~~said~~ data returned from said irradiation is ~~returned from said light and showed~~ shown on a monitor; and

wherein ~~analyzing~~ said data is analyzed to obtain said thickness of said wafer.